## REMARKS

Claims 21-31 are pending in the present application. The Examiner has rejected claims 23-24 and 26-31 under 35 U.S.C. § 103(a). The Examiner has also objected to claim 25. Applicants gratefully acknowledge the Examiner's indication that claims 21-22 are allowed. In light of the following remarks, reconsideration and allowance of this application are most respectfully requested.

## 35 U.S.C. § 103

Claims 23-24 and 26-31 stand rejected under 35 U.S.C. § 103(a) as being obvious over U.S. Patent No. 6,661,552 to Hira ("the Hira patent") in view of U.S. Patent No. 5,870,224 to Saitoh *et al.* ("the Saitoh patent"). As an initial matter, it is respectfully submitted that at least the Hira patent is not prior art relative to the present application. Applicants' perfected a priority claim on April 17, 2002, as acknowledged by the "Notice of Acceptance of Application under 35 U.S.C. 371 and 37 CFR 1.494 or 1.495" mailed on May 28, 2002. Applicants are therefore entitled to the priority date of April 29, 1999. The Hira patent was filed on September 5, 2002, and, on its face, claims a foreign priority date of October 18, 1999, *i.e.*, after Applicants' priority date. For at least this reason, the rejection of claims 23-24 and 26-31 under 35 U.S.C. § 103(a) over the Hira patent in view of the Saitoh patent, should be withdrawn.

Further, the Examiner concludes that "Saitoh teaches that it was known to provide aperture making up less than 10% of an opaque layer" (Office Action p. 3) in connection with Applicants' recited "an opaque layer having apertures making up less than 10% of the surface area of said opaque layer." The Examiner apparently relies on the statement in the Saitoh patent "that a screen with a bright image having an aperture

rate of 90% or grater is obtained in cases where (D'/D) is 10% or less." (Saitoh patent, col. 7, ll. 27-29.) Respectfully, Saitoh at most discloses the relationship between an aperture rate and the ratio of the *thickness* of a light blocking pattern to that of the lenticular sheet; Saitoh does not teach formation of an opaque layer having apertures making up less than 10% of the surface area of the opaque layer.

For at least the foregoing reasons, the rejection of claims 23-24 and 26-31 over the Hira patent in view of the Saitoh patent should be withdrawn.

## Claim Objection

The Examiner has objected to claim 25 as being dependent upon rejected base claim 23. The arguments presented above in connection with claim 23 and the Hira and Saitoh patents apply equally to claim 25. For at least this reason, the objection to claim 25 should be withdrawn.

Accordingly, it is therefore respectfully submitted that claim 25, along with claims 23-24 and 26-31, are in condition for immediate allowance.

## **Conclusion**

Each of the issues raised by the Examiner has been addressed. It is respectfully submitted that the present application is in condition for allowance. Passage to issuance is requested. The Examiner is invited to contact the undersigned at the telephone number below if he believes that the progress of this application could be advanced. The Commissioner is authorized to charge any additional fees or credit any overpayments under 37 C.F.R. §§ 1.16 and 1.17 to Deposit Account No. 11-0600.

Respectfully submitted, KENYON & KENYON

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